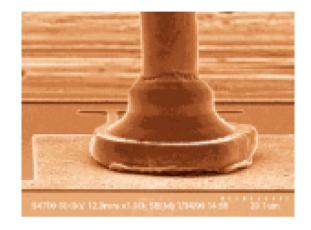
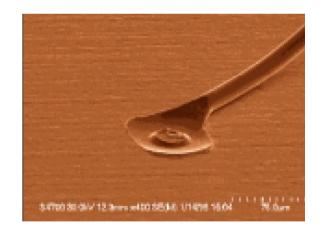


#### **ESCCON 2016**

Cu Wire Reliability Evaluation, Implications for Space Components





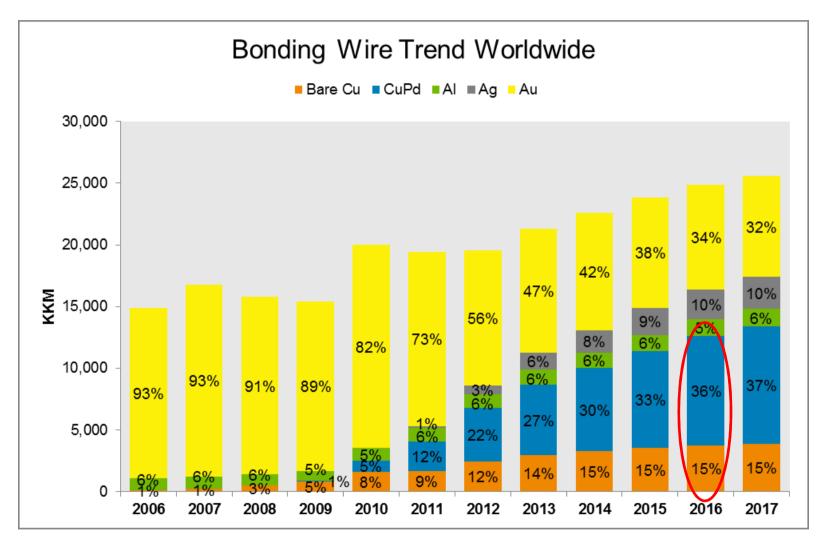
1 3<sup>rd</sup> Mar 2016

### **Summary**

- Wire Bonding Trend Worldwide
- Why Cu Wire?
- Why to replace Al Wire Bonding for Space Components?
- Cu or Au Wire Bonding?
- Known Cu Risks
- Cu Wire State of the Art
- Reliability Results
- Cu Wire Bonding applicable for Space Components?



# **Wire Bonding Trend Worldwide**

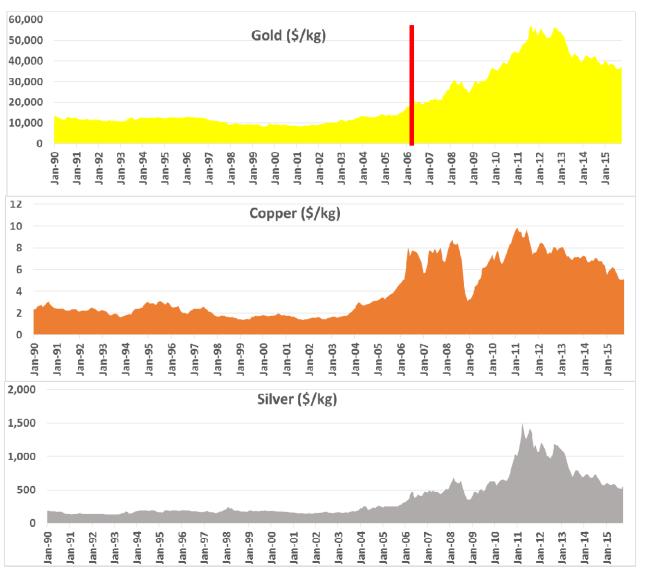


Source: SEMI Industry Research and StaMsMcs, November 2013



## Why Cu Wire?

#### Cost



~Gold/10,000

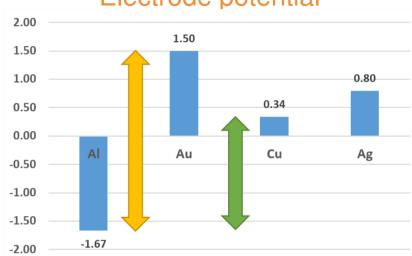
~Gold/100



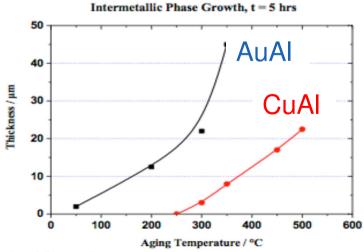
# Why Cu Wire?

#### **Technical Parameters**

### Electrode potential

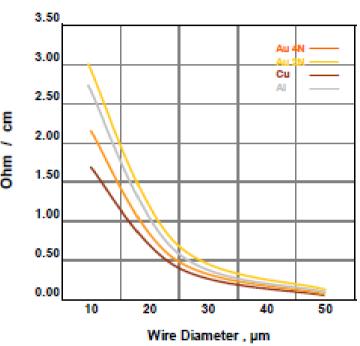


### Intermetallic growing



#### Electrical resistance

#### Resistance vs. Wire Diameter



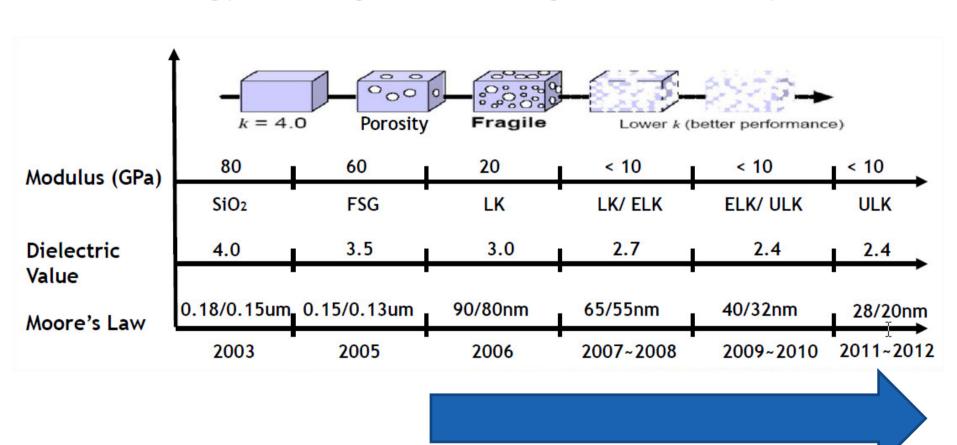
#### Thermal conductivity

Materia l of wire	Thermal Conductivity (W/m.K)	Comparis on
Gold	318	1
Copper	390	1.23



# Why to replace Al Wire Bonding for Space Components?

Si Technology Shrinkage ⇒ More Fragile Dielectric Layers



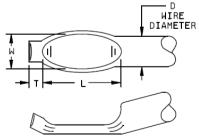


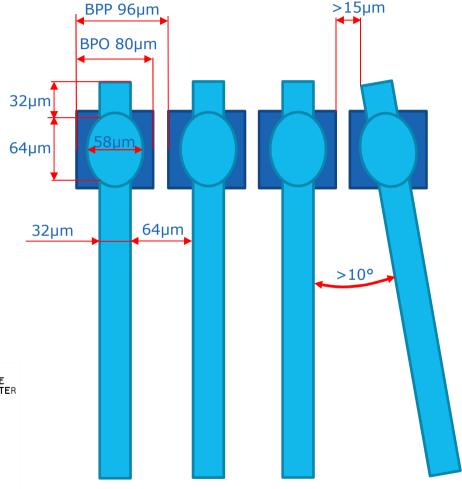
# Why to replace Al Wire Bonding for Space Components?

Si Technology Shrinkage ⇒ Lower Bonding Dimensions

- To Date (ATMEL 150nm)
  - Dielectric: SiO<sub>2</sub> FSG
  - Al wire diameter D= 32μm
  - Ultrasonic wedge bonding
    - Angle limitation
  - Min bond pad pitch: 96µm
    - 2 row staggered
    - 2D insulation: ≥64µm
  - Bond pad opening: 80μm
    - W std 1.8D= 58µm
    - L std 2D= 64µm
    - T std 1D= 32μm







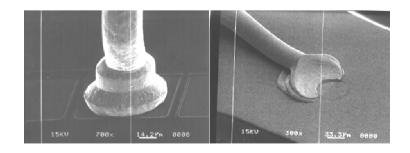


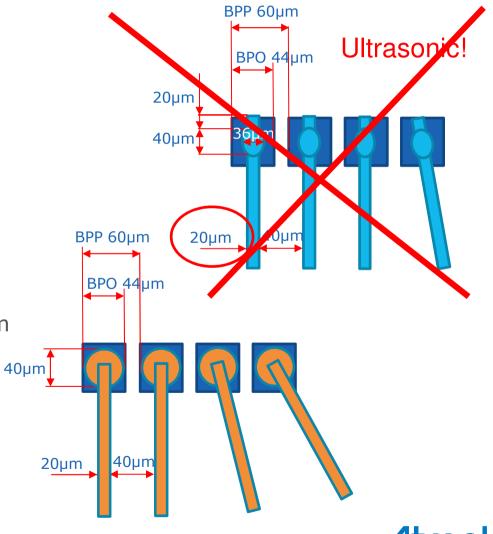
# Why to replace Al Wire Bonding for Space **Components?**

Si Technology Shrinkage 

Lower Bonding Dimensions

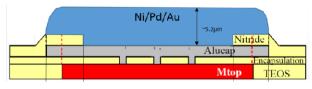
- To Come (65nm)
  - Dielectric: LowK
  - Wire diameter D= 20µm
  - Thermosonic ball bonding
    - No angle limitation
  - Min bond pad pitch: 60μm
    - 2 rows
    - 2D insulation
  - Bond pad opening: 44µm
  - Ball diameter min: 2D= 40μm





# Cu or Au Wire Bonding for Space Components?

- Au wire on Al bond pad
  - Intermetallic growing
    - Life-time 17 years @110°C?
  - Au/Al corrosion risk
    - Low in hermetic package
  - Tight process window
    - Intermetallic
  - Cost
  - Not Compliant with 883/level S
    - · Possibility for gold bumping



- Cu wire on Al bond pad
  - Low intermetallic growing
    - Life-time 17 years @110°C
  - Cu/Al corrosion risk
    - Low in hermetic package
  - Tight process window
    - Pad crack / Al splash
  - Low cost
  - Not Compliant with 883/level S

A.3.5.5.2 <u>Internal wire size and material</u>. For class level S microcircuits, the internal wire diameter shall be 0.001 inch minimum (0.0254 mm) or of sufficient diameter to meet the minimum fusing requirements and bond pull strength requirements with the approval of qualifying activity. The internal lead wire shall be the same metal as the diemetallization.

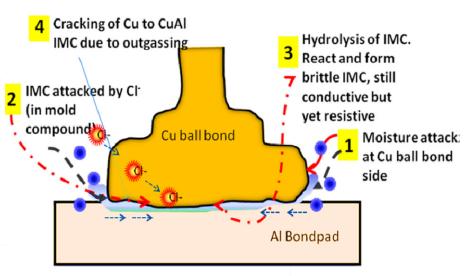


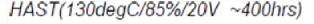
### **Known Cu Risks**

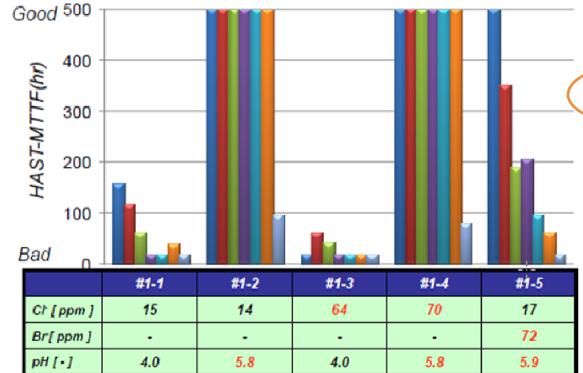
Hardness Pad Crack Al Splash Al thickness Position Au bonded balls Au FABs
 Cu bonded balls 130 Cu FABs Polynomial Fit 120 Hardness Hv0.01/5 90 80 70 60 Indenter Position from bonded ball center [µm]

#### **Known Cu Risks**

Corrosion - PH/Br/Cl//Moisture







PdCu > Cu bare PH > 5Br < 50ppm CI < 10ppm

ESA - ESCCON 2016 - D.Samson 3rd Mar 2016 **Atmel** 

■ Au wire

■PdCu wire

■ Cu bare wire

■Ag90% wire

■Ag92% wire

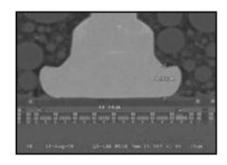
■Ag95% wire

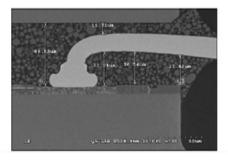
■Ag97% wire

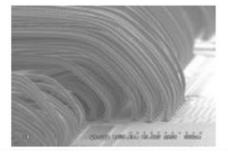
#### **Cu wire State of the Art**

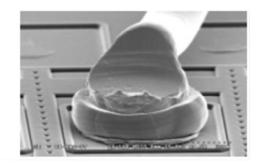
High Volume – Plastic Packages

- Wafer technology: 0.13 Cu/FSG 90/65/40/28/20nm LK/ELK
- Bond pad structure: CUP structure
- Bond pad pitch (BPP): ≥ 40µm
- Bond Pad opening (BPO): ≥35µm
- Cu wire diameter:  $\geq 15\mu m/0.6$  mils
- Bond pad layout: in line, staggered, up to, 5 tiers, Pad to Pad
- Low loop height: 45µm
- Wire count: > 1500











# **Reliability Results**

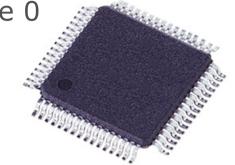
Example: LQFP176 - Automotive AEC-Q100 Grade 0

Body Size: 24x24x1.2mm

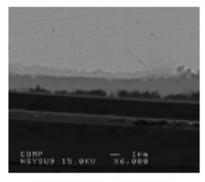
Lead Count: 176

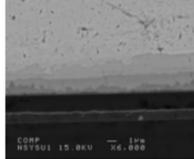
Wafer process: LowK - 65nm

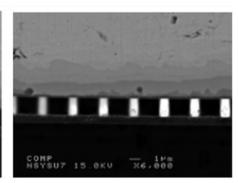
Cu wire diameter: 0.8 mils/20µm



	Result	Requirements	Sample Size	Analysis required
Precon: MSL @ 260°C	Pass L3	L3	0/77	NA
Precon + TC -65/+175°C Precon + TC -50/+150°C	Pass 500x Pass 2000x	500x 2000x	0/45	5 unit wire pull/ball shear after decap
HTS 175°C (no precon) HTS 150°C (no prcon)	Pass 1000hrs Pass 2000hrs	1000hrs 2000hrs	0/77	NA
Precon + uHAST (121/130)	Pass 96hrs	96hrs	0/77	NA
Precon + THB 85/85	Pass 1000hrs	1000hrs	0/77	NA







HTST 300hrs (@225C)

HTST 500hrs (@225C)

HTST 1000hrs (@225C)



# Cu Wire Bonding applicable for Space **Components?**

- Hermetic Ceramic Packages: YES
  - CuPd (PCC)
  - PH > 5
  - Br < 10ppm

  - $H_2O < 5000ppm$
  - Al Thickness ≥ 1.0µm
  - DOE to each new device (tight parameters window)
  - Cu wire option to allow in MIL or ESCC

A.3.5.5.2 Internal wire size and material. For class level S microcircuits, the internal wire diameter shall be 0.001 inch minimum (0.0254 mm) or of sufficient diameter to meet the minimum fusing requirements and bond pull strength requirements with the approval of qualifying activity. The internal lead wire shall be the same metal as the die metallization.

- Molded Packages: YES but
  - Halogen free materials (BGA substrate die attach molding compound) - compliant with ECSS-Q-ST-70-02 outgassing standard
  - Br/Cl lot to lot content stability in materials
  - Sensitivity to moisture (HAST)
  - Dry pack/MSL level to apply?







© 2015 Atmel Corporation.

Atmel®, Atmel logo and combinations thereof, Enabling Unlimited Possibilities®, and others are registered trademarks or trademarks of Atmel Corporation or its subsidiaries. Other terms and product names may be trademarks of others.

Disclaimer: The information in this document is provided in connection with Atmel products. No license, express or implied, by estoppel or otherwise, to any intellectual property right is granted by this document or in connection with the sale of Atmel products. EXCEPT AS SET FORTH IN THE ATMEL TERMS AND CONDITIONS OF SALES LOCATED ON THE ATMEL WEBSITE, ATMEL ASSUMES NO LIABILITY WHATSOEVER AND DISCLAIMS ANY EXPRESS, IMPLIED OR STATUTORY WARRANTY CREATION FOR TIST PRODUCTS INCLUDING, BUT NOT LIMITED TO, THE IMPLIED WARRANTY OF MERCHANTABILITY, FITNESS FOR A PARTICULAR PURPOSE, OR NON-INFRINGEMENT. IN NO EVENT SHALL ATMEL BE LIABLE FOR ANY DIRECT, INDIRECT, INDIRECT, INDIRECT, INDIRECT, EVEN POUNTINE, SPECIAL OR INCIDENTAL DAMAGES (INCLUDING, WITHOUT), DAMAGES FOR LOSS AND PROFITS, BUSINESS INTERRUPTION, OR LOSS OF INFORMATION). ARISING OUT OF THE USE OR INABILITY TO USE THIS DOCUMENT, EVEN IF ATMEL HAS BEEN ADVISED OF THE POSSIBILITY OF SUCH DAMAGES. Atmel makes no representations or warranties with respect to the accuracy or completeness of the contents of this document and reserves the right to make changes to specifications and products descriptions at any time without notice. Atmel does not make any commitment to update the information contained herein. Unless specifically provided otherwise, Atmel products are not suitable for, and shall not be used in, automotive applications. Atmel products are not intended, authorized, or warranted for use as components in applications intended to support or sustain life.

15 © 2016 Atmel Corporation ESA - ESCCON 2016 - D.Samson 3<sup>rd</sup> Mar 2016